

Available online at www.sciencedirect.com



Journal of the European Ceramic Society 26 (2006) 1917–1920

www.elsevier.com/locate/jeurceramsoc

Preparation and tunability properties of $Ba(Zr_xTi_{1-x})O_3$ thin films grown by a sol–gel process

Jiwei Zhai^{a,*}, Dan Hu^a, Xi Yao^a, Zhengkui Xu^b, Haydn Chen^b

^a Functional Materials Research Laboratory, Tongji University, Siping Road 1239, Shanghai 200092, China ^b Department of Physics and Materials Science, City University of Hong Kong, Kowloon, Hong Kong

Available online 17 October 2005

Abstract

Ba(Zr_xTi_{1-x})O₃ (BZT) thin films were deposited via sol-gel process on LaNiO₃, as buffer layer, and Pt-coated silicon substrates. The BZT films were perovskite phase and showed a (1 0 0) preferred orientation dependent upon zirconium content. The grain size decreased and the microstructure became dense with increasing zirconium content. The addition of Zr to the BaTiO₃ lattice decreased the grain size of the crystallized films. The temperature dependent dielectric constant revealed that the thin films have relaxor behavior and diffuse phase transition characteristics that depend on the substitution of Zr for Ti in BaTiO₃. The dependence of electrical properties on film thickness has been studied, with the emphasis placed on dielectric nonlinear characteristics. Ba($Zr_{0.35}Ti_{65}$)O₃ thin films with weak temperature dependence of tunability in the temperature range from 0 to 130 °C could be attractive materials for situations in which precise control of temperature would be either impossible or too expensive. © 2005 Elsevier Ltd. All rights reserved.

Keywords: Sol-gel processes; Films; Perovskites; Dielectric properties; Tunability

1. Introduction

Ba(Zr_xTi_{1-x})O₃ ceramics and thin films have recently received renewal attention due to a high-strain level and highpiezoelectric effect in both single crystals and ceramics.¹⁻⁴ In addition, the results indicate that the system exhibits a pinched phase transition with increasing Zr concentration. It is obtained by substituting ions at the B site of the BaTiO₃ with Zr in compounds of the perovskite structure ABO₃. It is reported that an increase in the Zr content induces a reduction in the average grain size, decreases the dielectric constant, and maintains a leakage current low and stable. This is possible because the Zr⁴⁺ ion has larger ionic size (0.087 nm) than Ti⁴⁺(0.068 nm).^{3,4}

Ba $(Ti_{1-x}Zr_x)O_3$ materials have an orthorhombic or rhombohedral structure at room temperature.^{5,6} It is expected that the enhanced dielectric performance can be also achievable at around room temperature in the $\langle 100 \rangle$ preferred orientation BZT thin films. Since Ba $(Ti_{1-x}Zr_x)O_3$ films may be applied to capacitors, tunable microwave devices, actuators, and dynamic random access memories because they are environment-friendly,

0955-2219/\$ - see front matter © 2005 Elsevier Ltd. All rights reserved. doi:10.1016/j.jeurceramsoc.2005.09.021

it is important to investigate the tunability and effect of thickness on the dielectric properties.

In this paper, we report on $BaZr_xTi_{1-x}O_3$ thin film deposition on LaNiO₃, as buffer layer on Pt/Ti/SiO₂/Si substrates and analyze the relationship of composition, microstructure, and dielectric behavior of the thin films. Dielectric properties of the thin films are studied as a function of thickness, temperature, and electric field.

2. Experimental

The barium acetate $[Ba(CH_3COO)_2]$, $[Zr(OC_3H_7)_4]$, and $[Ti(OC_3H_7)_4]$ were used as starting materials. Acetic acid was used as solvent. $Ba(CH_3COO)_2$ was heated and dissolved in acetic acid. Zirconium isopropoxide and titanium isopropoxide were mixed in a ratio according to a predetermined number $(Ba(Zr_xTi_{1-x})O_3, x=0, 0.05, 0.18, and 0.35)$, and then dissolved into heated glacial acetic acid. After cooling to room temperature, ethylene glycol CH₂OHCH₂OH was added to control the viscosity and cracking of films; the solution was mixed and refluxed for 1 h. Barium acetate was added in glacial acetic acid solution and heated to $120 \,^{\circ}$ C to reflux for 1 h. Ba:glacial acetic acid was in a ratio equal to $1:10 \,\text{mol. After cooling to room temperature, the mixed solution of Ti(OC₃H₇)₄,$

^{*} Corresponding author. Tel.: +86 21 65980544; fax: +86 21 65985179. *E-mail address:* zhaijiwei@eastday.com (J. Zhai).

Zr(OC₃H₇)₄, and acetylacetone (AcAc CH₃COCH₂COCH₃) was added slowly under continuous stirring in the solution ((Ti+Zr):AcAc = 1:2 mol). Finally, 2-methoxyethanol and ethylene glycol were added to control the viscosity, cracking of films and the concentration of solution. The concentration of the final solution was adjusted to about 0.3 M. After aging the hydrolyzed solution for 24 h, thin film deposition was carried out on the LaNiO₃/Pt/Ti/SiO₂/Si(1 0 0) substrates by spin coating at 3000 rpm for 30 s each layer. Each spin-coated BZT layer was subsequently heat treated at 500 °C for 5 min. The coating and heat treatment procedures were repeated several times until the desired thickness was reached. A final anneal in flowing O₂ at high temperature of 700 °C for 30 min crystallize the amorphous films.

The crystalline phase of the thin films was identified by Xray diffraction (SIEMENS D-500 powder diffractometer). The film thickness and the surface morphology were determined by FESEM. For electrical measurements, the top gold electrode of a 200 μ m square was deposited by DC-sputtering. The capacitance–voltage (*C*–*V*) and capacitance–temperature (*C*–*T*) characteristics were measured using an Agilent 4284A LCR meter. The sample's temperature was varied by using a Delta chamber.

3. Results and discussion

Fig. 1 shows the XRD patterns for the BZT thin films. It is evident that the BZT films are polycrystalline. Perovskite peaks were observed for all the films of different composition. It is evident that the BZT films were perovskite phase and had (100) preferred orientation when deposited on LNO/Pt/ Ti/SiO₂/Si(100) substrate. The insert shows BZT(200) peaks in a magnified angular scale. A slight shift of the (200) plane is shown in the inset of Fig. 1. A gradual shift of 2θ angles to the low angle side with increasing Zr content in the BZT films



Fig. 1. XRD patterns of sol-gel deposited $BaZr_xTi_{1-x}O_3$ thin films on LaNiO₃/Pt/Ti/SiO₂/Si(100): (a) x=0, (b) x=0.05, (c) x=0.18, and (d) x=0.35.

reveals the expansion of perovskite lattice by the addition of the Zr in BaTiO₃. The grain size decreased and the microstructure became dense with increasing of zirconium content. The addition of Zr to the BaTiO₃ lattice decreased the grain size of the crystallized films.

The dielectric constant and dielectric loss of x = 0.05 and x = 0.35 composition thin films as a function of temperature and frequency are show in Fig. 2. With increasing zirconium content, the characteristics of diffuse phase transition were increased. With increase in Zr content to x = 0.35, the ferroelectric behavior of the thin films changes to a relaxor-like character. The broadening of transition together with the shift of the Curie temperature towards higher temperature in thin films of normal ferroelectrics ceramics was due to the influence of the interfaces in the films,⁷ the fine grained structure,⁸ and unrelaxed growth strain.^{9,10}



Fig. 2. The dielectric constant and dielectric loss of $BaZr_xTi_{1-x}O_3$ thin films: (a) x = 0.05 and (b) x = 0.35, as a function of temperature and frequency.



Fig. 3. ϵ -*E* characteristics of BaZr_{0.35}Ti_{0.65}O₃ thin films for different thickness: (a) 150 nm, (b) 200 nm, (c) 320 nm, (d) 480 nm, and (e) 660 nm (measurement frequency 100 kHz).

Fig. 3 shows the room temperature dielectric constant versus electric field characteristics as a function of BZT film thickness. Dielectric constant and dielectric loss of the films was measured at 100 kHz, with an AC field of 0.4 kV/cm superimposed on a slowly varying DC bias field. The DC bias was stepped through 0.2 V intervals and held 1 s prior to capacitance measurement. The loss tangent measurements as a function of bias voltage gave curves of similar shape to the tuning curves. Losses for all samples were less than 2% at room temperature and zero bias. The zero-field dielectric constant decreased systematically with increasing film thickness, while at higher fields, the dielectric constant was also thickness dependent, not consistent with previous observations.^{8,11} We will discuss this phenomenon in another paper.

The shape of the $\epsilon - E$ curves change and depend on the thickness. The $\epsilon - E$ characteristics are noticeably different in the positive and negative voltage region, especially for the thinner films. This asymmetry of the $\epsilon - E$ characteristic is due to the film/substrate interface effects, consistent with previous reports.^{12,13}

It is revealed that the BZT possesses high tunability even in the paraelectric phase. The dielectric constant tunability of the films can be expressed as $(\epsilon(0) - \epsilon(E))/\epsilon(0)$. The tunability of BaZr_{0.35}Ti_{0.65}O₃ films for different thickness is about 42%, at an applied field of 400 kV/cm and measurement frequency of 100 kHz. These values are comparable to those of polycrystalline BST thin films.¹⁴ The existence of polar-clusters and their coarsening with increasing temperature may be one of the reasons for the tunability of dielectric constant in BZT thin films.¹⁵

The dielectric constant and dielectric loss of x = 0.35 composition thin films as a function of temperature and thickness are show in Fig. 4. The data reveal a relatively flat profile, in the range of temperature from 0 to $130 \,^{\circ}$ C, for BaZr_{0.35}Ti_{0.65}O₃ films having different thickness. As expected, there is no steep change occurring in this range of temperature due to parelectric state.

Fig. 5 shows the temperature dependence of dielectric constant as a function of externally applied DC voltage for the



Fig. 4. The dielectric constant and dielectric loss of $BaZr_{0.35}Ti_{0.65}O_3$ thin films for different thickness: (a) 150 nm, (b) 200 nm, (c) 320 nm, and (d) 660 nm, as a function of temperature (measurement frequency 100 kHz).



Fig. 5. Temperature dependence of the measured dielectric constant at zero-field and 375 kV/cm for the thickness of 320 nm sample (measurement frequency 100 kHz).

Ba(Zr_{0.35}Ti₆₅)O₃ thin films, measured at 100 kHz. All show a relatively flat profile under different DC bias field in the temperature range of 0-130 °C. The change of dielectric constant versus DC bias field is quite appreciable, indicating a high tunability over a wide temperature range.

Generally, ferroelectric material is tunable in only a narrow temperature range near a phase transition. $BaZr_{0.35}Ti_{0.65}O_3$ thin film with weak temperature dependence of tunability could make attractive materials for situations in which precise control of temperature would be either impossible or too expensive.

4. Conclusions

The Ba(Zr_xTi_{1-x})O₃ (x=0, 0.05, 0.15, and 0.35) thin films were deposited via sol-gel process on LaNiO₃-coated silicon substrates. The films were of single perovskite phase and had (100) preferred orientation. The temperature dependent dielectric measurements revealed that the thin films have relaxor behavior and diffuse phase transition characteristics dependent upon zirconium content. It was revealed that the $BaZr_{0.35}Ti_{0.65}O_3$ possess high tunability even in the paraelectric phase. The tunability of $BaZr_{0.35}Ti_{0.65}O_3$ films for different thickness is about 42%, at an applied field of 400 kV/cm and measurement frequency of 100 kHz. The zero-field dielectric constant decreased systematically with increasing film thickness. Generally, ferroelectric material is tunable in only a narrow temperature range near a phase transition. $BaZr_{0.35}Ti_{0.65}O_3$ thin film with weak temperature dependence of tunability could be attractive materials for situations in which precise control of temperature would be either impossible or too expensive.

Acknowledgements

This research was supported by the Ministry of Sciences and Technology of China through 973-project under grant 2002CB613304, Shanghai Nano Fundamental Committee and the Scientific Research Foundation for the Returned Overseas Chinese Scholars.

References

- Farhi, R., Marssi, M. E., Simon, A. and Ravez, J., A Raman and dielectric study of ferroelectric Ba(Ti_{1-x}Zr_x)O₃ ceramics. *Eur. Phys. J. B*, 1999, 9, 599–604.
- Zhi, Y., Guo, R. and Bhalla, A. S., Dielectric behavior of Ba(Ti_{1-x}Zr_x)O₃ single crystals. J. Appl. Phys., 2000, 88, 410–415.
- Wu, T. B., Wu, C. M. and Chen, M. L., Highly insulative barium zirconate-titanate thin films prepared by rf magnetron sputtering for dynamic random access memory applications. *Appl. Phys. Lett.*, 1996, 69, 2659–2661.
- Dixit, A., Majumder, S. B., Savvinov, A., Katiyar, R. S., Guo, R. and Bhalla, A. S., Investigations on the sol-gel-derived barium zirconium titanate thin films. *Mater. Lett.*, 2002, 56, 933–937.

- Rehrig, P. W., Park, S. E., Mckinstry, S. T., Messing, G. L., Jones, B. and Shrout, T. R., Piezoelectric properties of zirconium-doped barium titanate single crystals grown by templated grain growth. *J. Appl. Phys.*, 1999, 86, 1657–1661.
- Yu, Z., Guo, R. and Bhalla, A. S., Growth of Ba(Ti_{1-x}Zr_xTiO₃ single crystals by the laser heated pedestal growth technique. *J. Cryst. Growth*, 2001, 233, 460–465.
- Qu, B., Zhong, W. and Zhang, P. L., Phase-transition behavior of the spontaneous polarization and susceptibility of ferroelectric thin films. *Phys. Rev. B*, 1994, **52**, 766–770.
- Parker, C. B., Maria, J. P. and Kingon, A. I., Temperature and thickness dependent permittivity of (Ba,Sr)TiO₃ thin films. *Appl. Phys. Lett.*, 2002, 81, 340–342.
- Bhaskar, S., Majumder, S. B. and Katiyar, R. S., Diffuse phase transition and relaxor behavior in (PbLa)TiO₃ thin films. *Appl. Phys. Lett.*, 2002, 80, 3997–3999.
- Carlson, C. M., Rivkin, T. V., Parilla, P. A., Perkins, J. D. and Ginley, D. S., Large dielectric constant (ε/ε₀ > 6000) Ba_{0.4}Sr_{0.6}TiO₃ thin films for high-performance microwave phase shifters. *Appl. Phys. Lett.*, 2000, **76**, 1920–1922.
- Basceri, C., Streiffer, S. K., Kingon, A. I. and Waser, R., The dielectric response as a function of temperature and film thickness of fiber-textured (Ba,Sr)TiO₃ thin films grown by chemical vapor deposition. *J. Appl. Phys.*, 1997, **82**, 2497–2504.
- Lee, S. Y. and Tseng, T. Y., Electrical and dielectric behavior of MgO doped Ba_{0.7}Sr_{0.3}TiO₃ thin films on Al₂O₃ substrate. *Appl. Phys. Lett.*, 2002, **80**, 1797–1799.
- Abe, K. and Komatsu, S., Ferroelectric properties in epitaxially grown Ba_xSr_{1-x}TiO₃ thin films. *J. Appl. Phys.*, 1995, 77, 6461– 6465.
- Knauss, L. A., Pond, J. M., Horwitz, J. S., Chrisely, D. B., Mueller, C. H. and Treece, R., The effect of annealing on the structure and dielectric properties of Ba_xSr_{1-x}TiO₃ ferroelectric thin films. *Appl. Phys. Lett.*, 1996, **69**, 25–27.
- Zhai, J. W., Yao, X., Shen, J., Zhang, L. Y. and Chen, H., Structural and dielectric properties of Ba(Zr_xTi_{1-x})O3 thin films prepared by the sol-gel process. *J. Phys. D: Appl. Phys.*, 2004, **37**, 748–752.